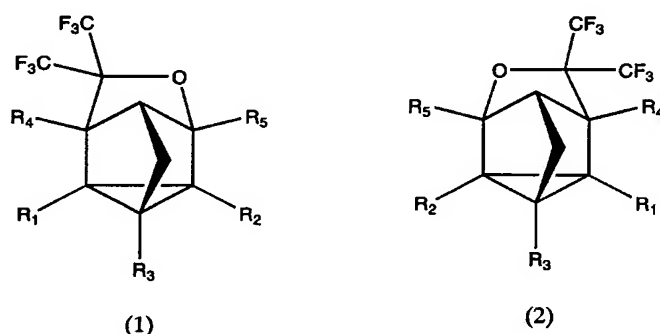


**Amendments to the Claims:**

The following listing of claims replaces all prior versions, and listings, of claims in the application:

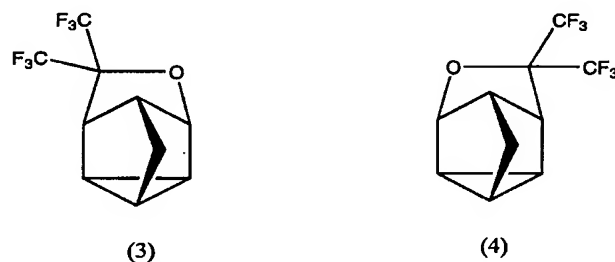
**Listing of Claims:**

1. (previously presented) A fluorine-containing cyclic compound represented by the following formula (1) or (2),

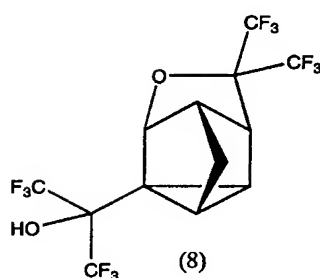
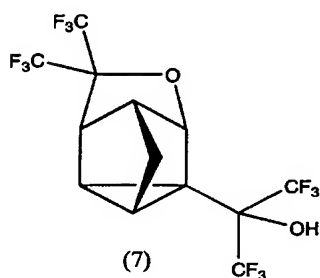
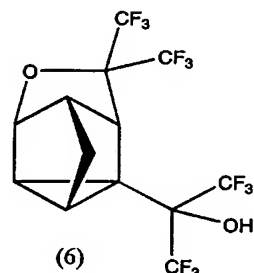
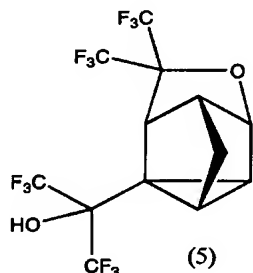


wherein, in the formulas (1) and (2), each of R<sub>1</sub>, R<sub>2</sub>, R<sub>3</sub>, R<sub>4</sub> and R<sub>5</sub> is independently selected from the group consisting of hydrogen, alkyl group, hydroxyl group, halogen atom, halogenated alkyl group, carbinol group, and hexafluorocarbinol group; wherein the hexafluorocarbinol group contained in the formula may be partially or entirely protected; and wherein the protecting group is a straight-chain, branched or cyclic hydrocarbon group of a carbon number of 1-25 or a group containing an aromatic hydrocarbon group and may contain at least one of fluorine atom, oxygen atom, nitrogen atom and carbonyl bond.

2. (original) A fluorine-containing cyclic compound represented by the following formula (3) or (4).



3. (original) A fluorine-containing cyclic compound represented by one of the following formulas (5) to (8).



4-14. (canceled)

15. (previously presented) A fluorine-containing cyclic compound according to claim 1, wherein the hexafluorocarbino group contained in the fluorine-containing cyclic compound is partially or fully protected with an acid-labile group.

16. (previously presented) A fluorine-containing high-molecular compound prepared by a polymerization or copolymerization of at least a fluorine-containing cyclic compound according to claim 1.

17. (original) A resist material using a fluorine-containing high-molecular compound according to claim 16.

18. (original) A pattern forming process using a resist material according to claim 17.